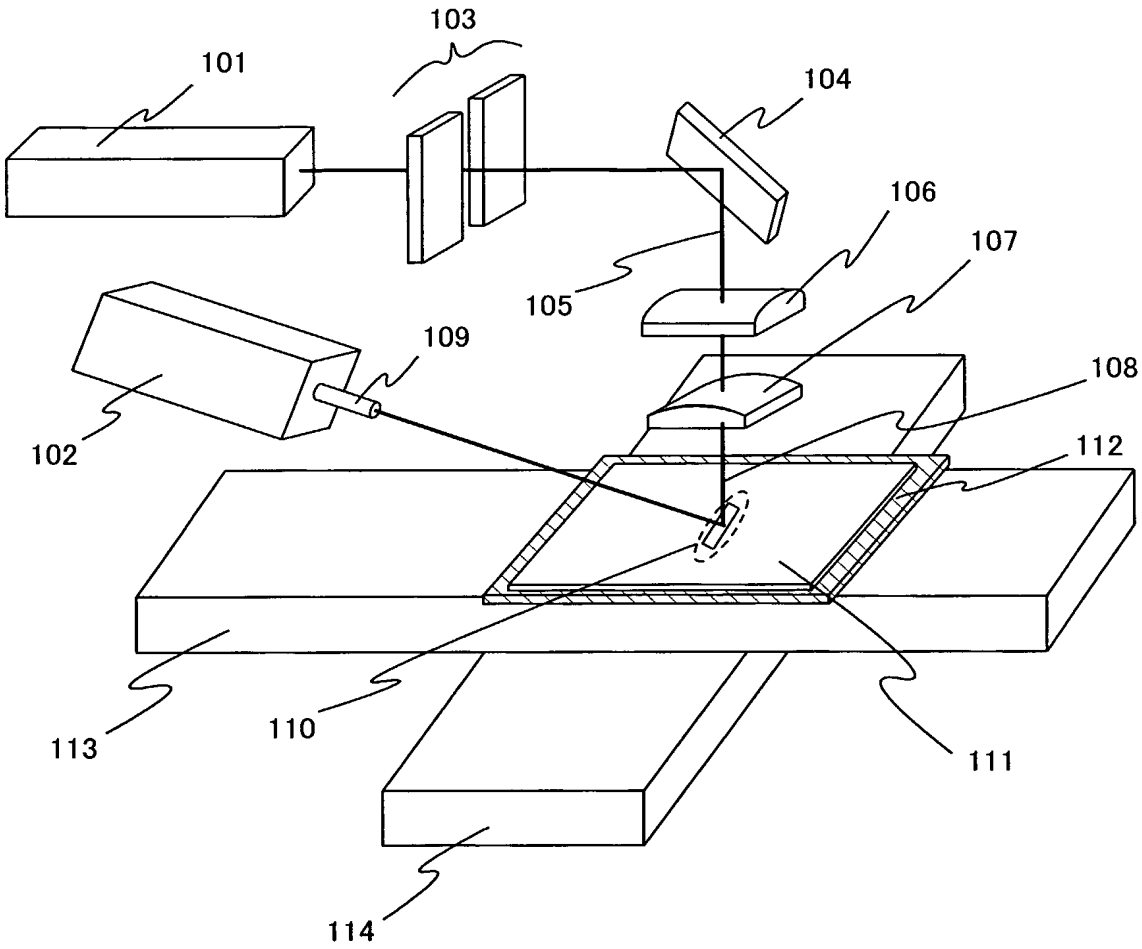


FIG. 1

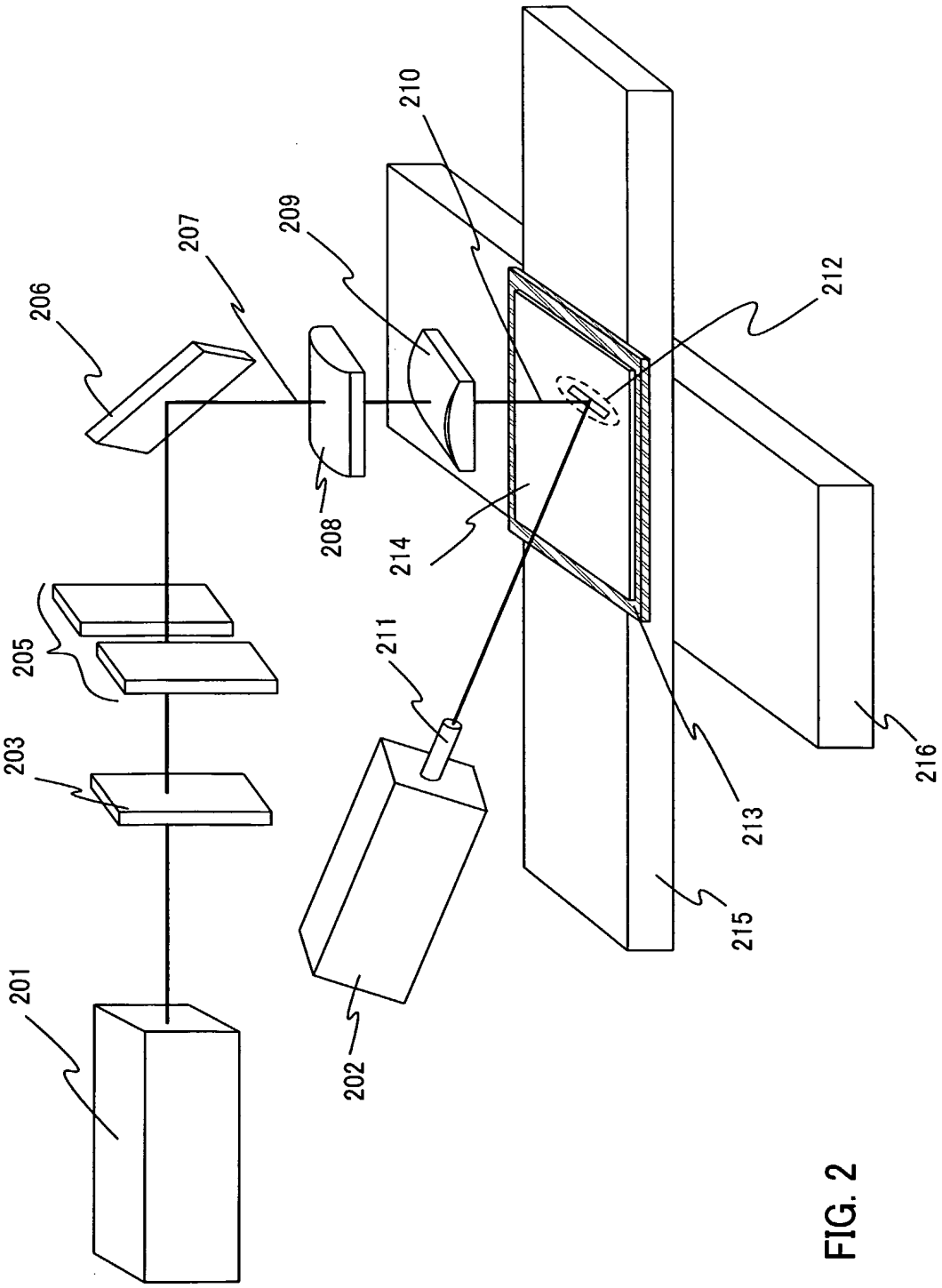


FIG. 2

FIG. 3A

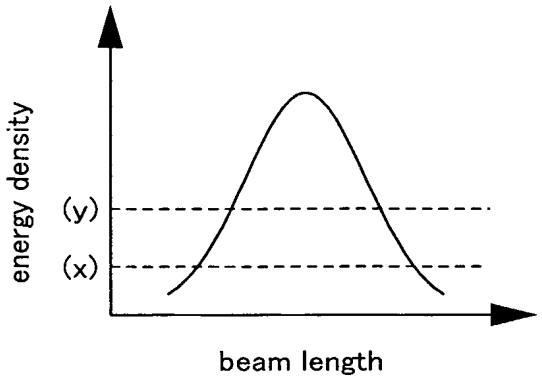


FIG. 3B

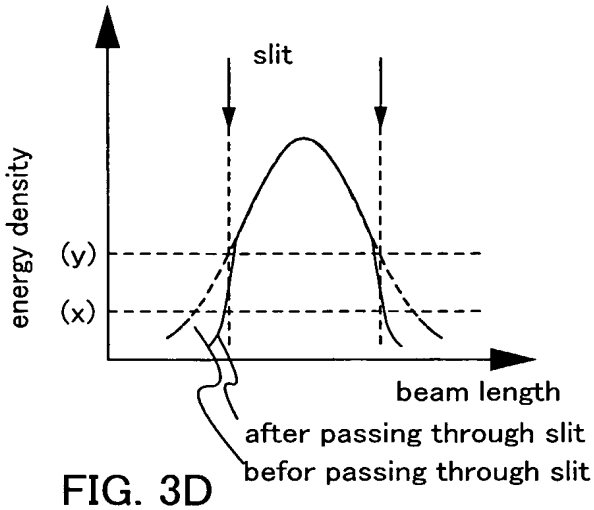


FIG. 3C

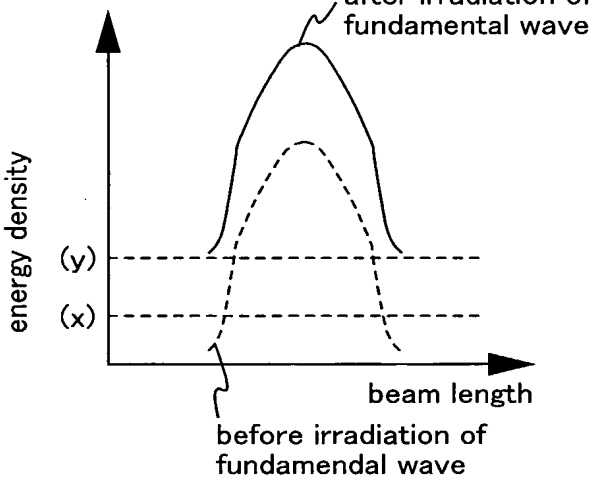


FIG. 3D

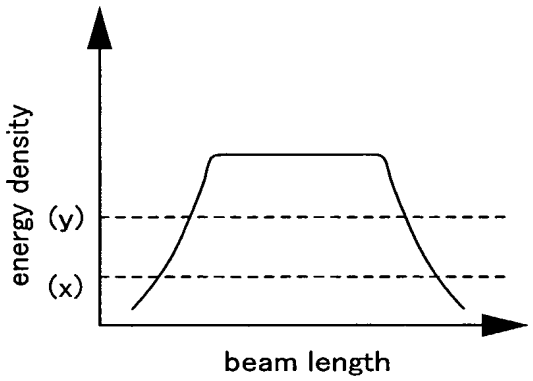


FIG. 3E

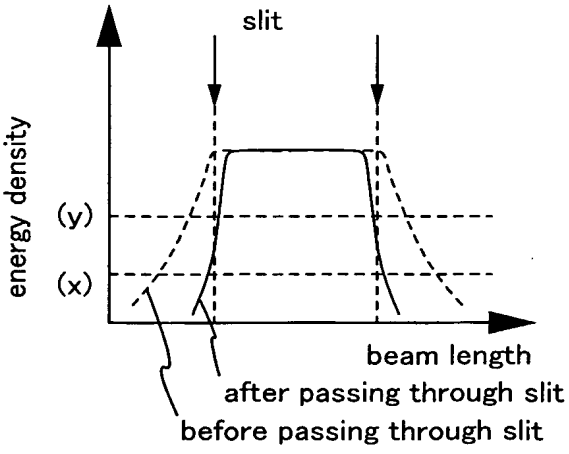
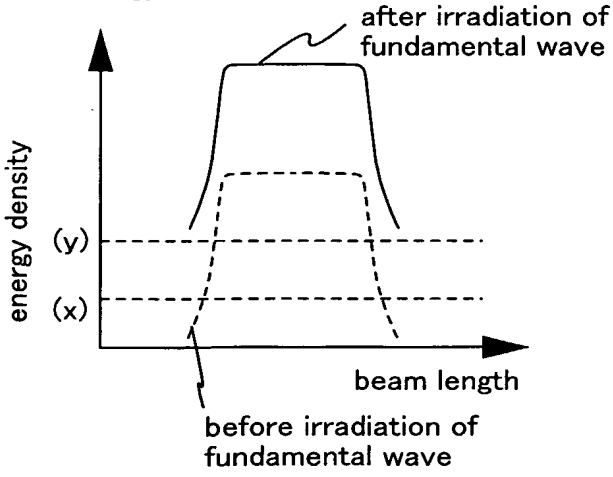


FIG. 3F



(x) threshold at which crystalline region is formed
(y) threshold at which crystalline region having large crystal grain is formed

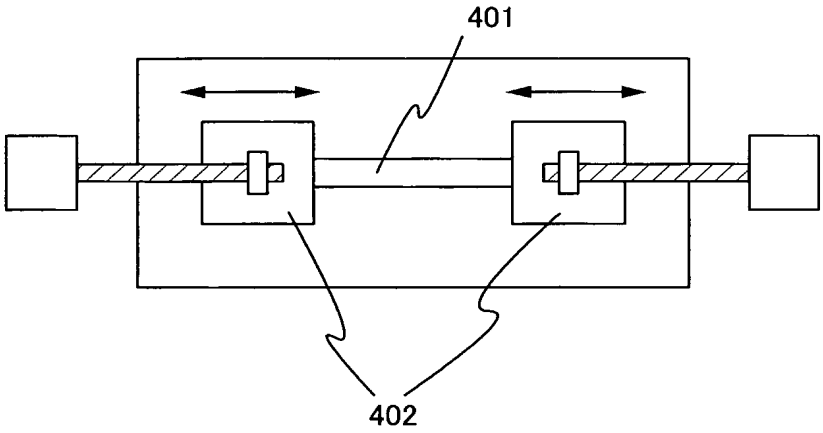


FIG. 4

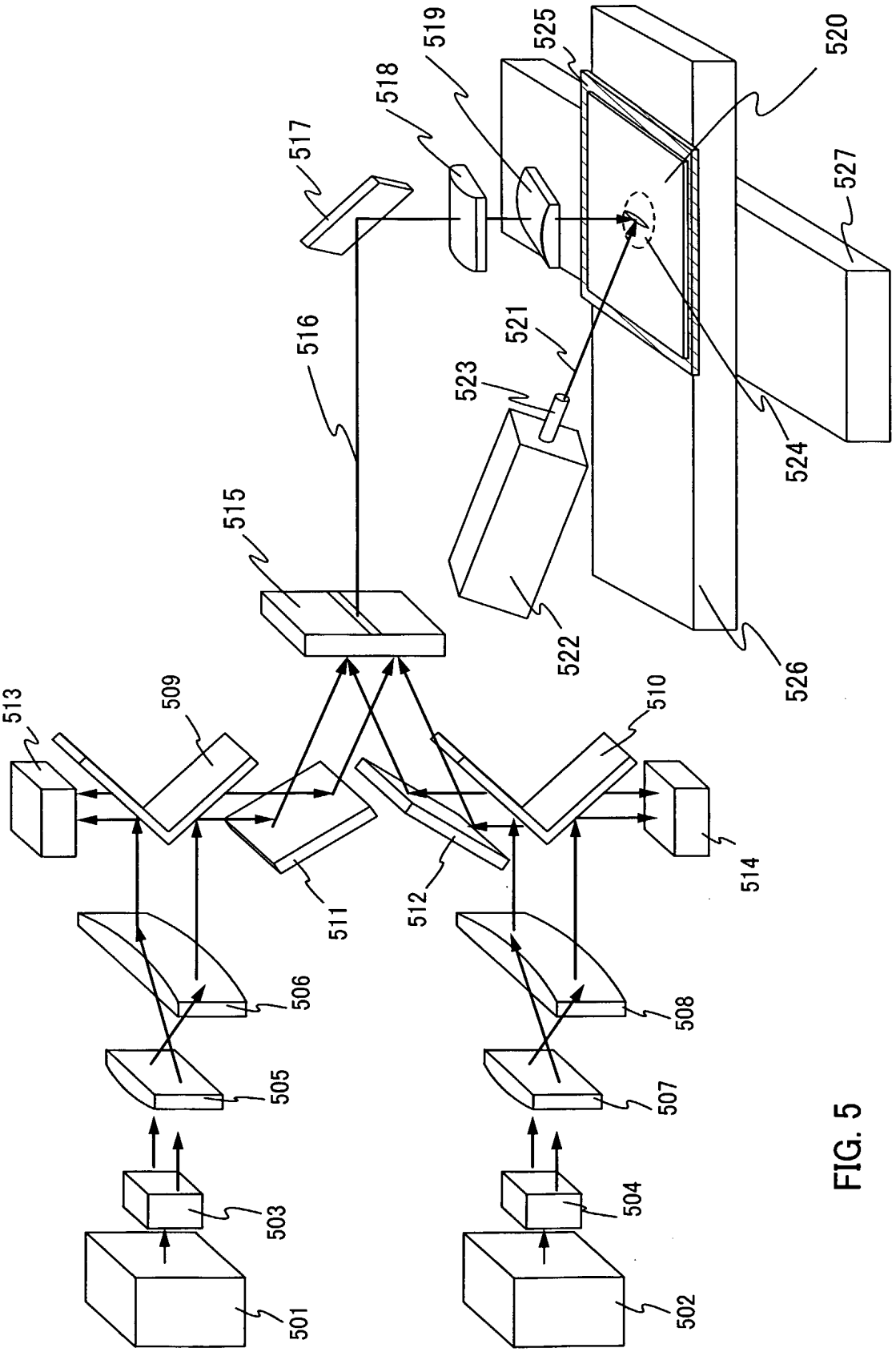

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FIG. 5

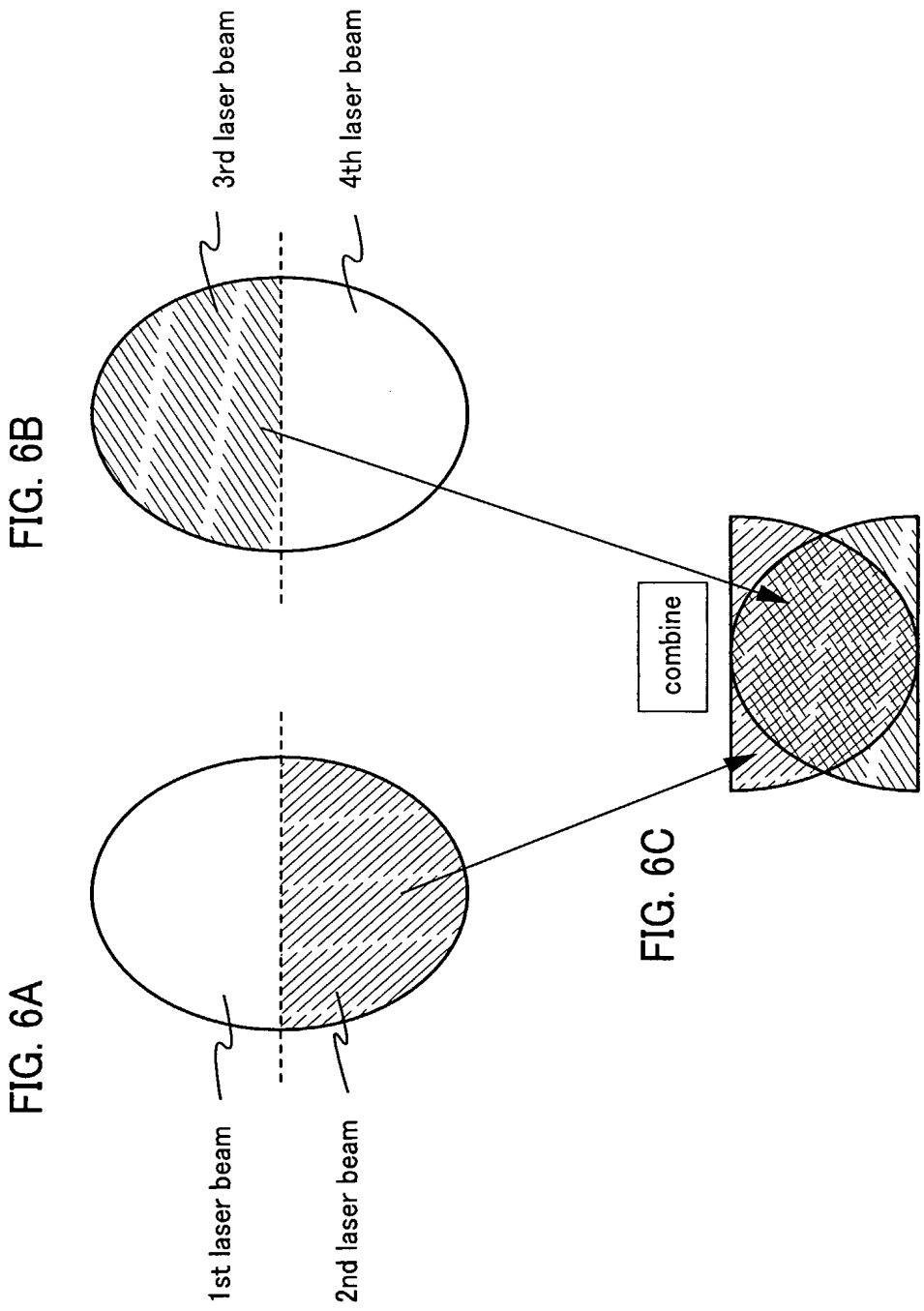


FIG. 6A

FIG. 6B

FIG. 6C

FIG. 7A

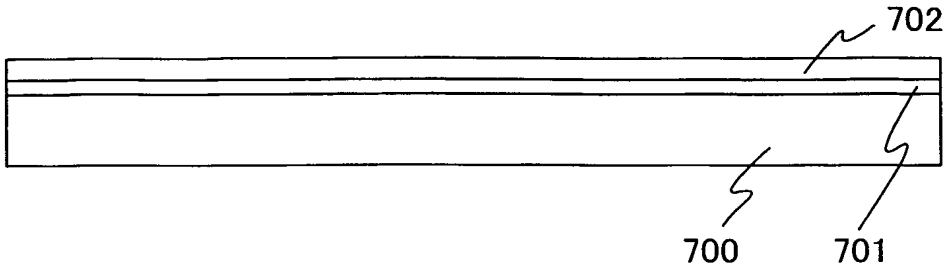


FIG. 7B

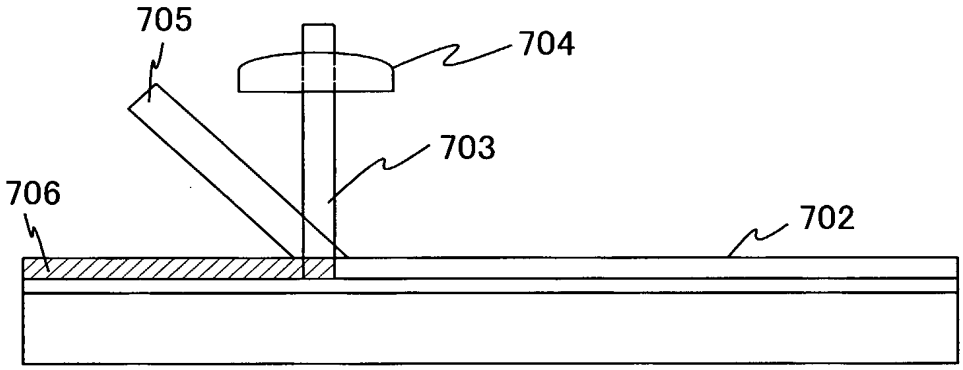


FIG. 7C

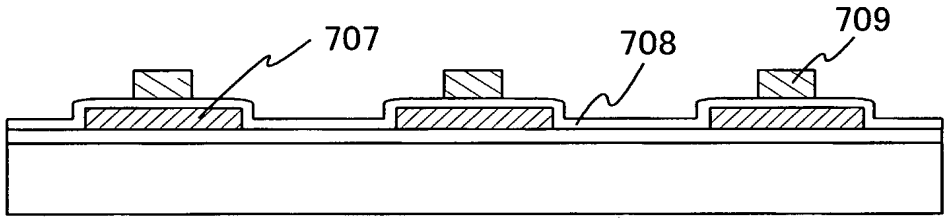


FIG. 7D

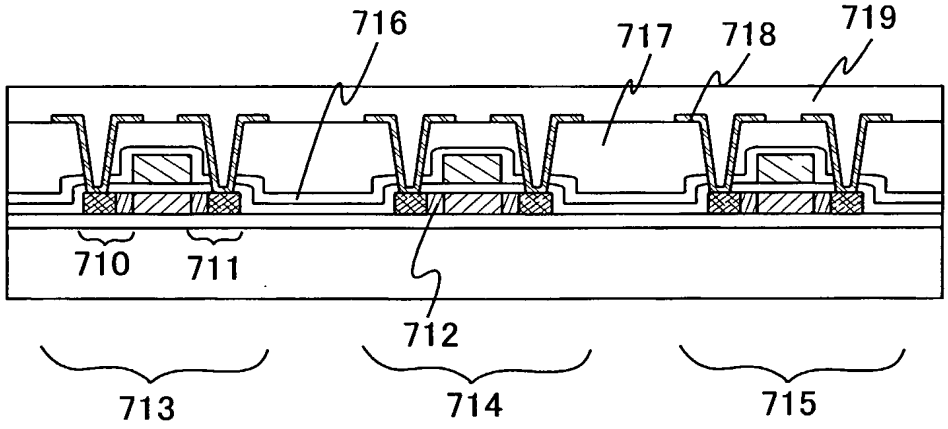
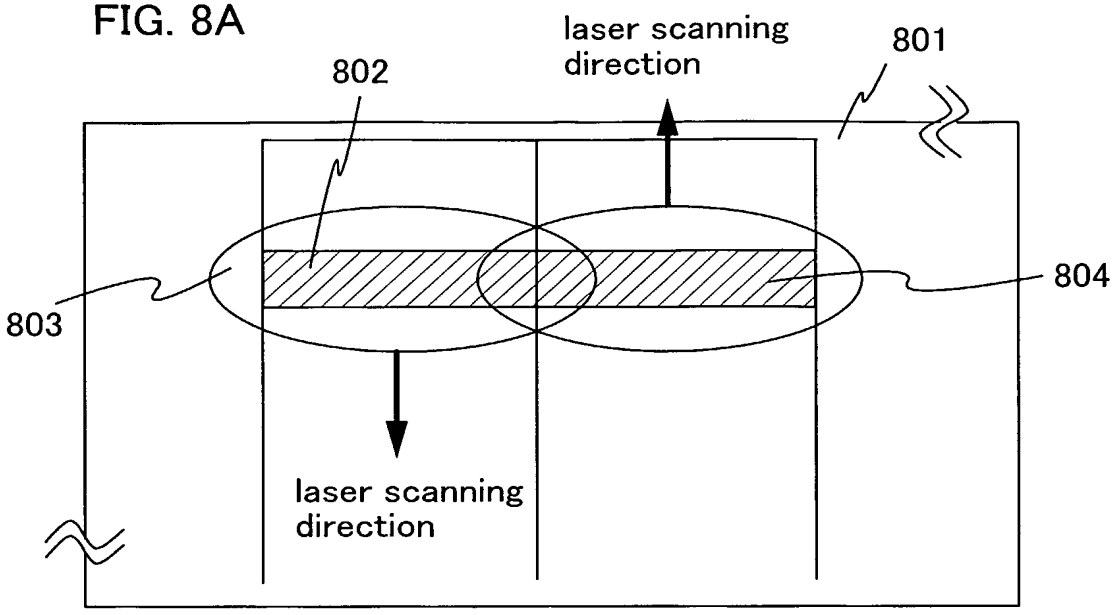


FIG. 8A


laser scanning direction
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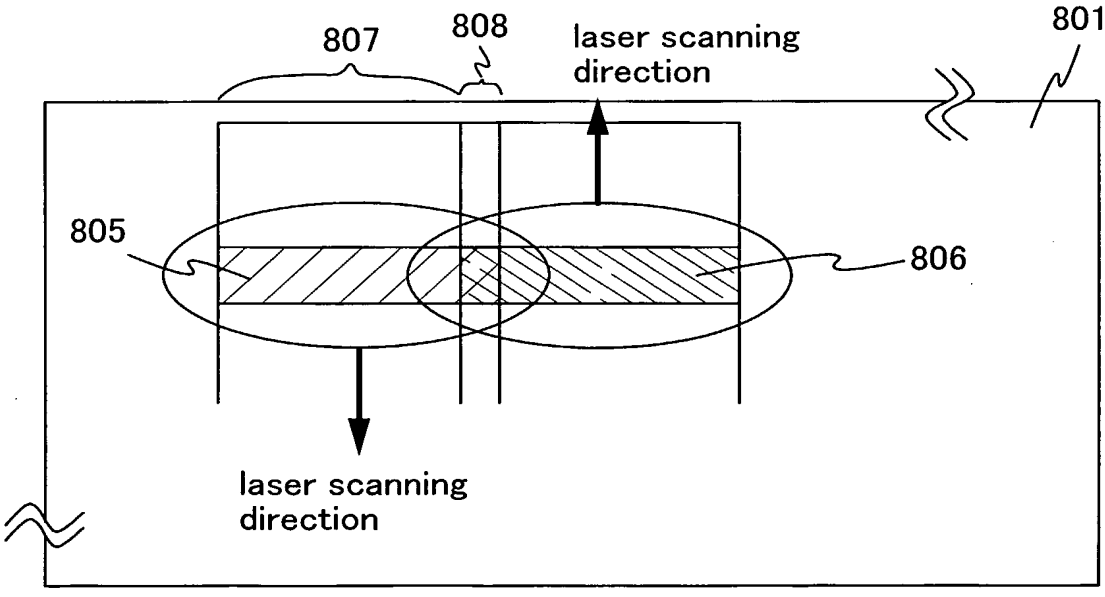
laser scanning direction

FIG. 8B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laser scanning direction
801
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806
laser scanning direction

FIG. 9A

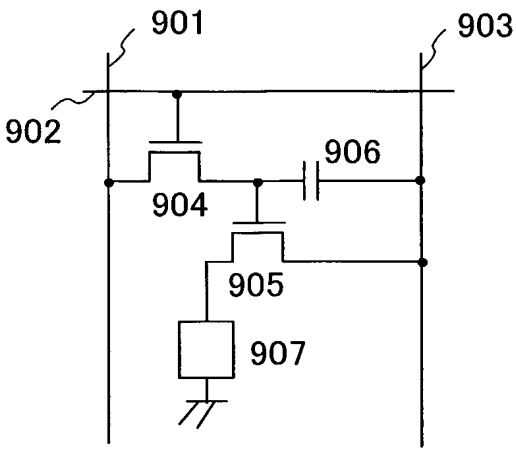


FIG. 9B

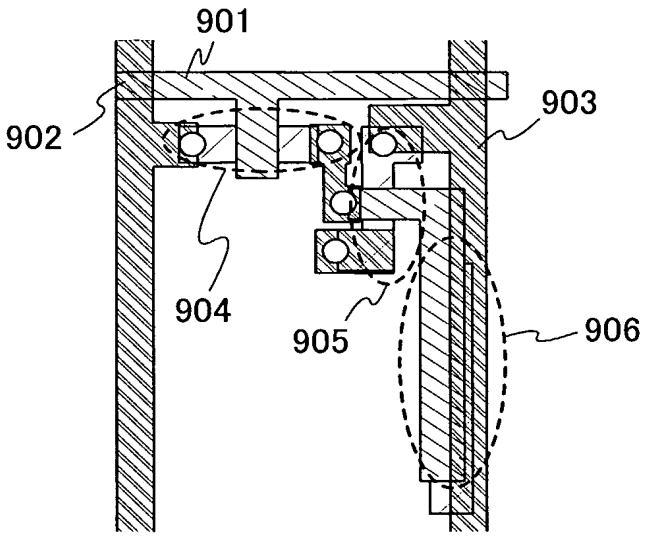


FIG. 9C

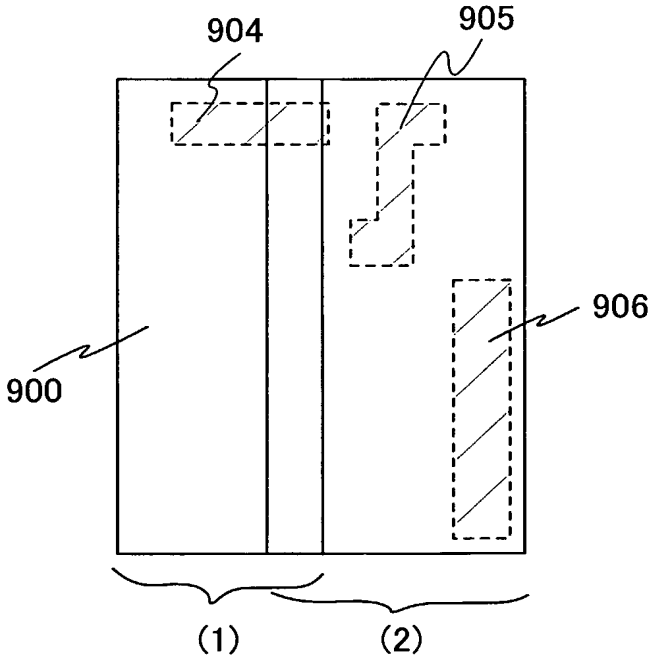


FIG. 10A

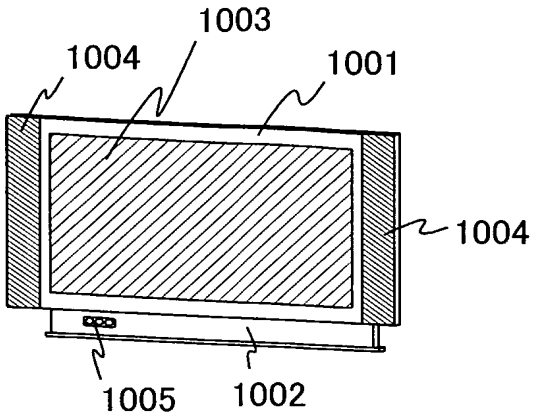


FIG. 10B

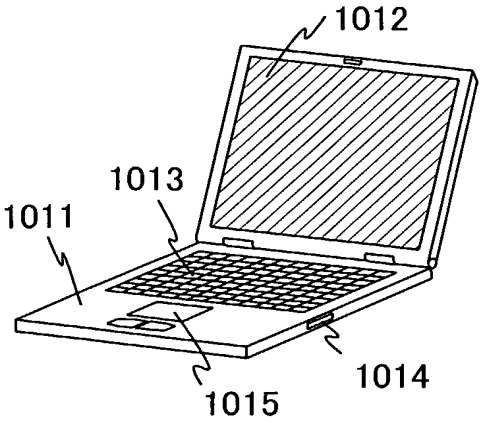


FIG. 10C

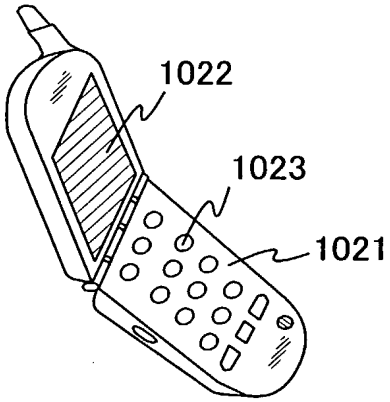


FIG. 10D

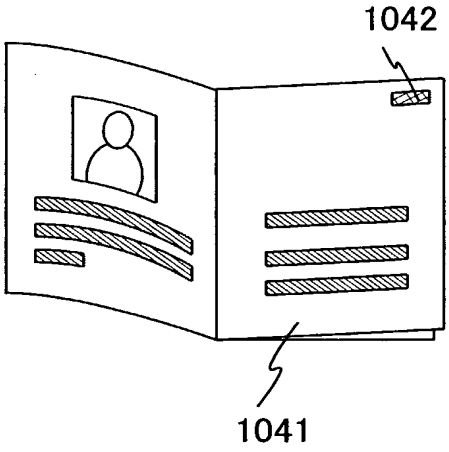
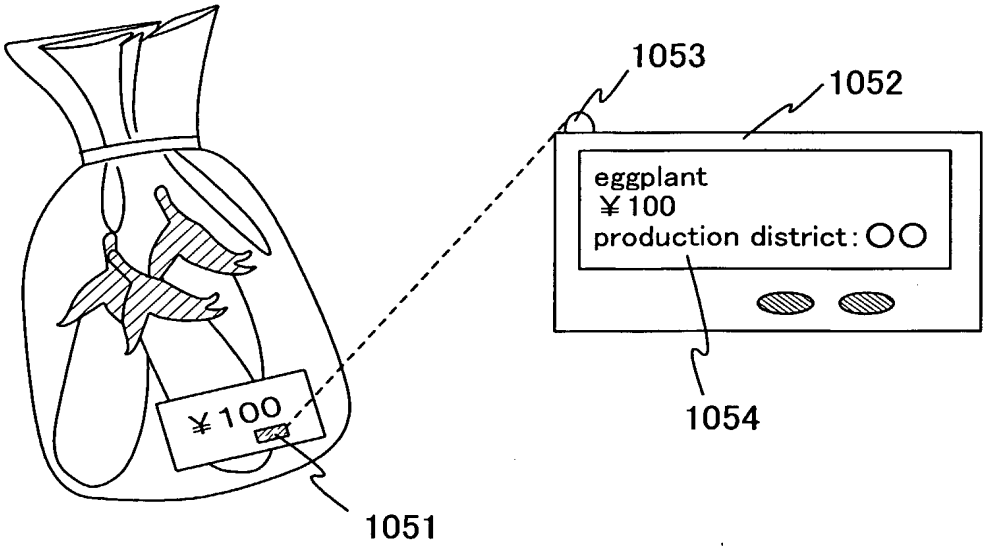
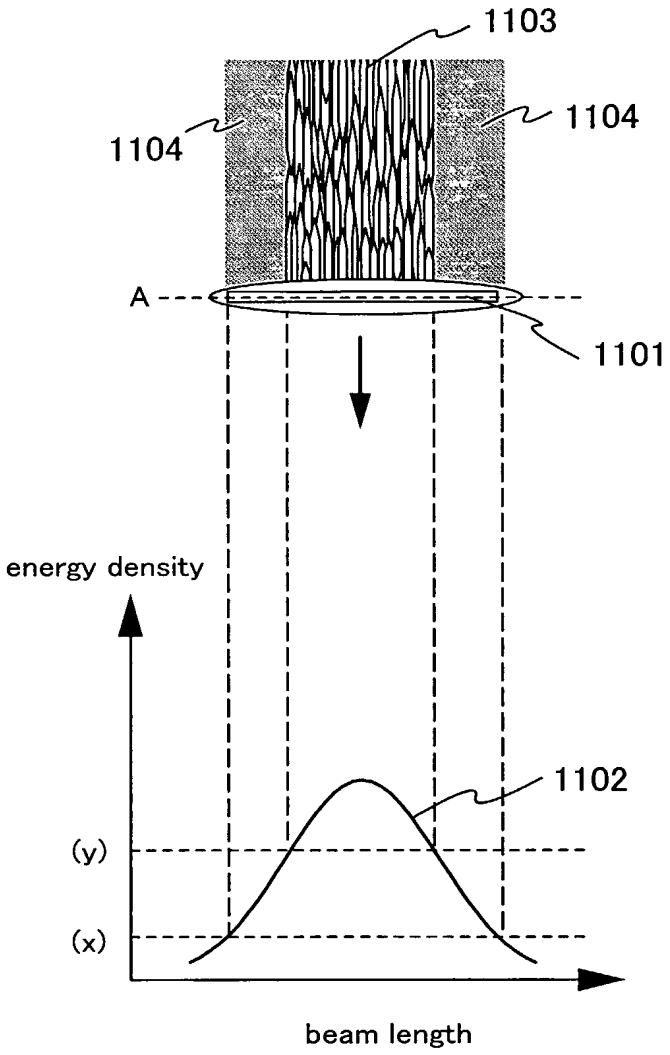


FIG. 10E





(x) threshold at which crystalline region is formed

(y) threshold at which crystalline region having large crystal grain is formed

FIG. 11

FIG. 12A

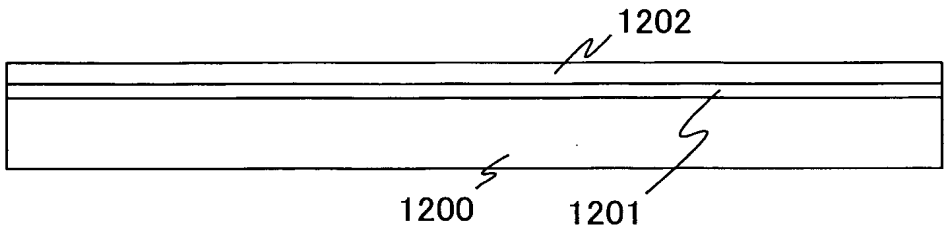


FIG. 12B

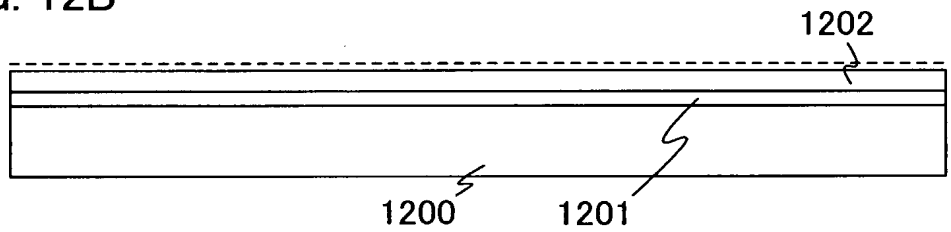


FIG. 12C

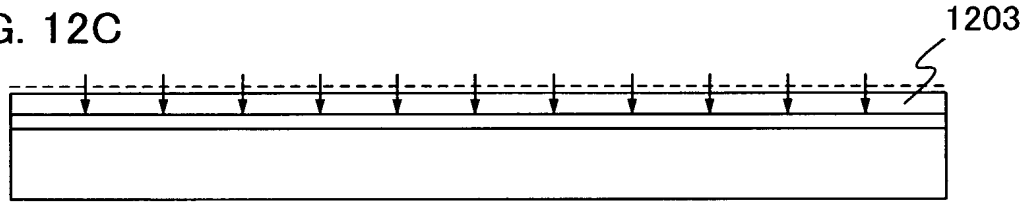


FIG. 12D

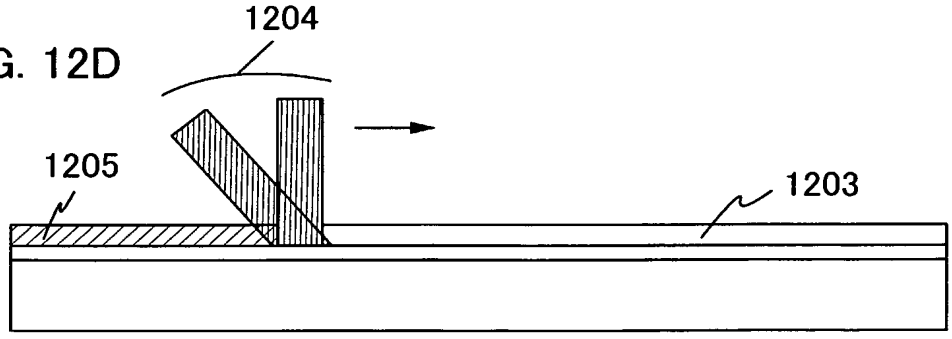


FIG. 13A

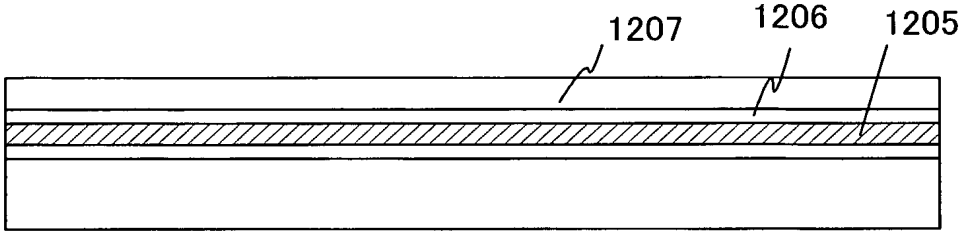


FIG. 13B

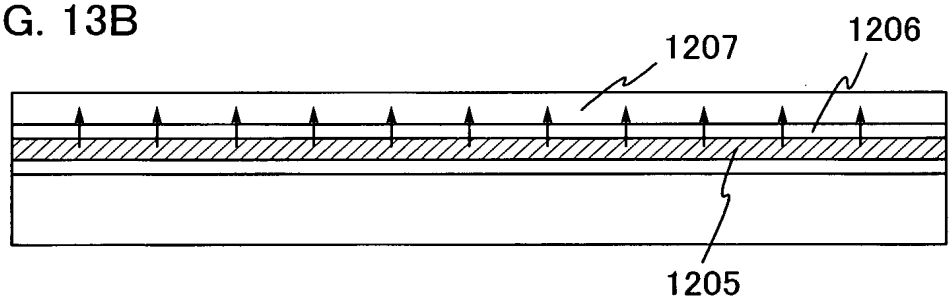


FIG. 13C

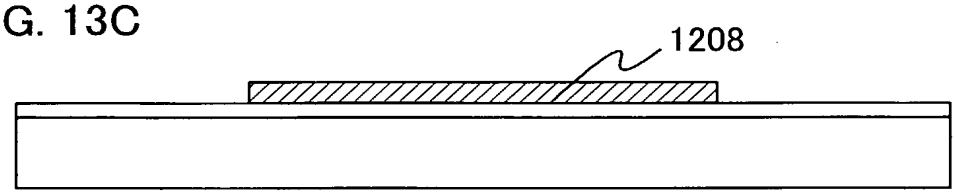


FIG. 14A

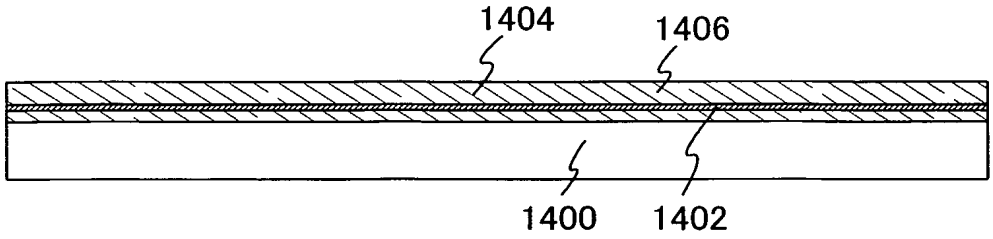


FIG. 14B

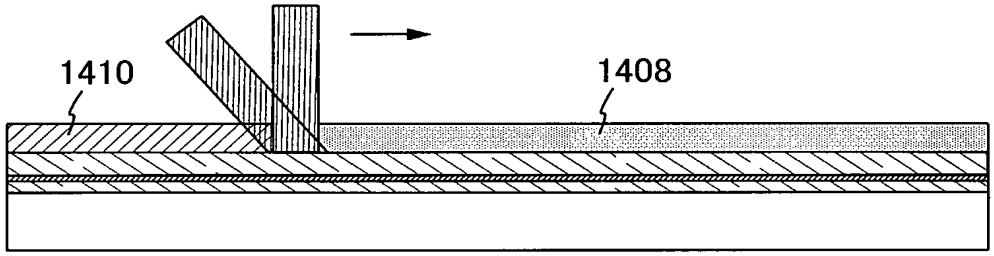


FIG. 14C

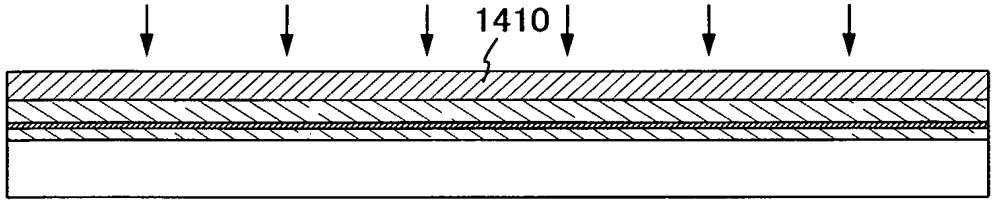


FIG. 14D

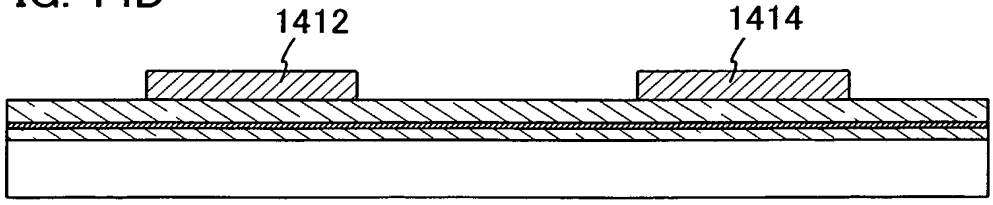


FIG. 15A

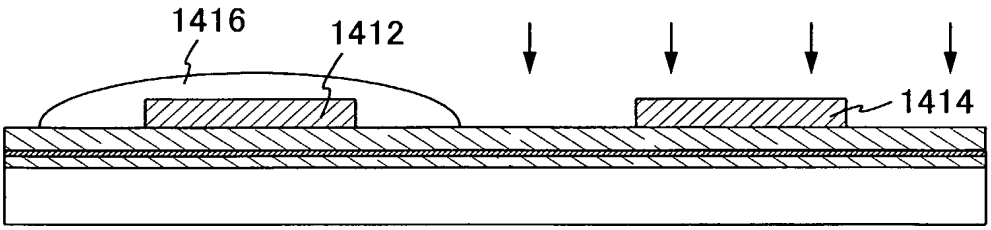


FIG. 15B

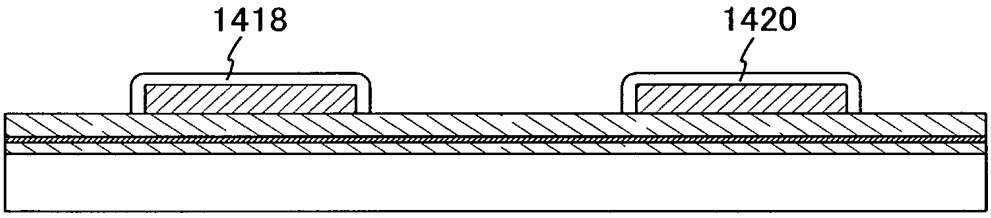


FIG. 15C

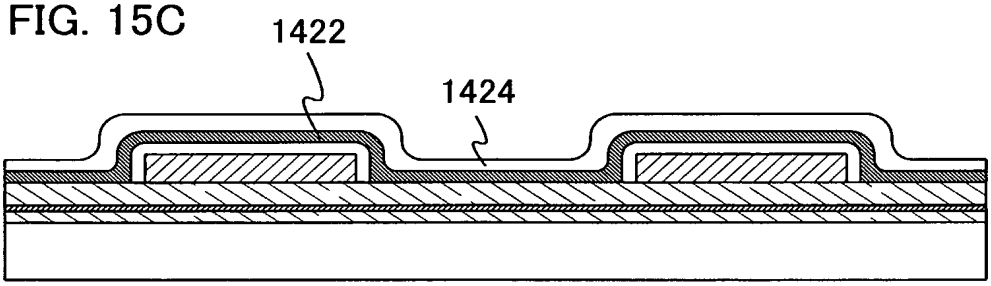


FIG. 15D

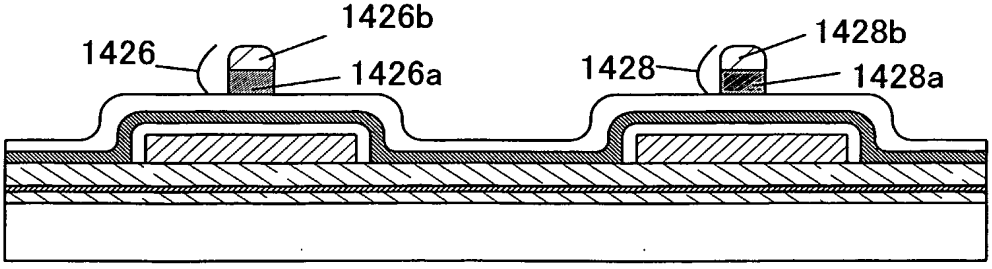


FIG. 16A

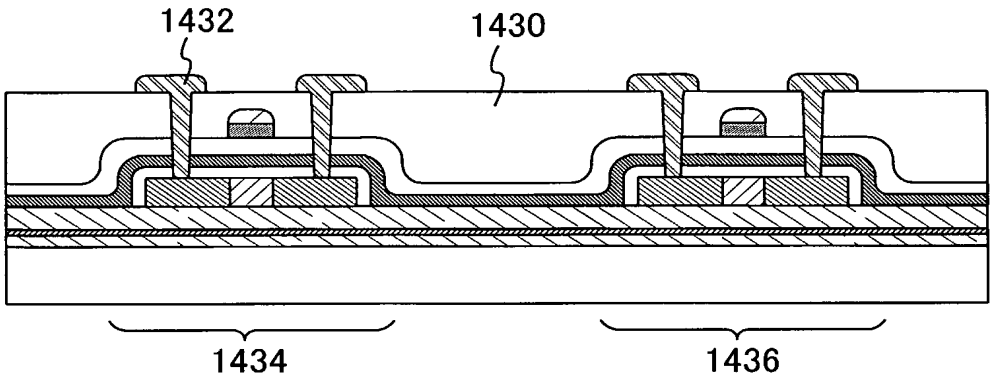
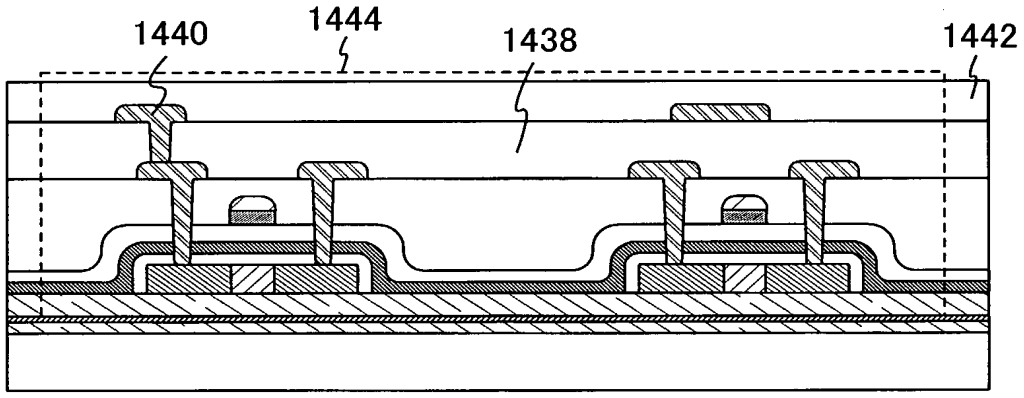


FIG. 16B



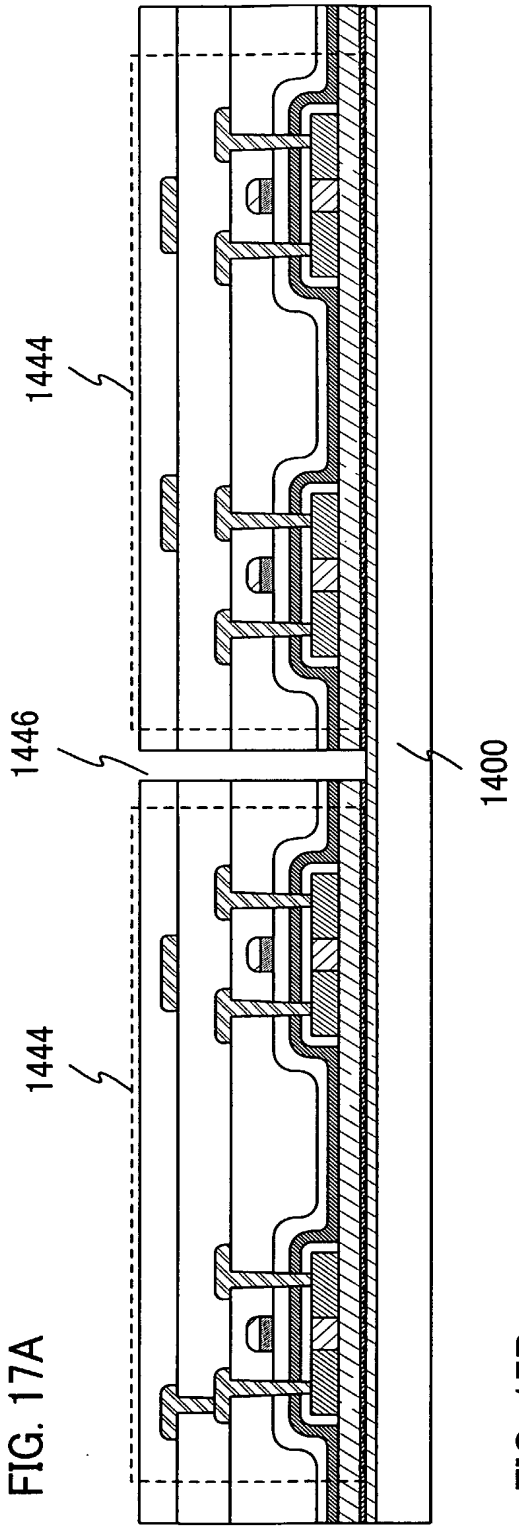


FIG. 17A

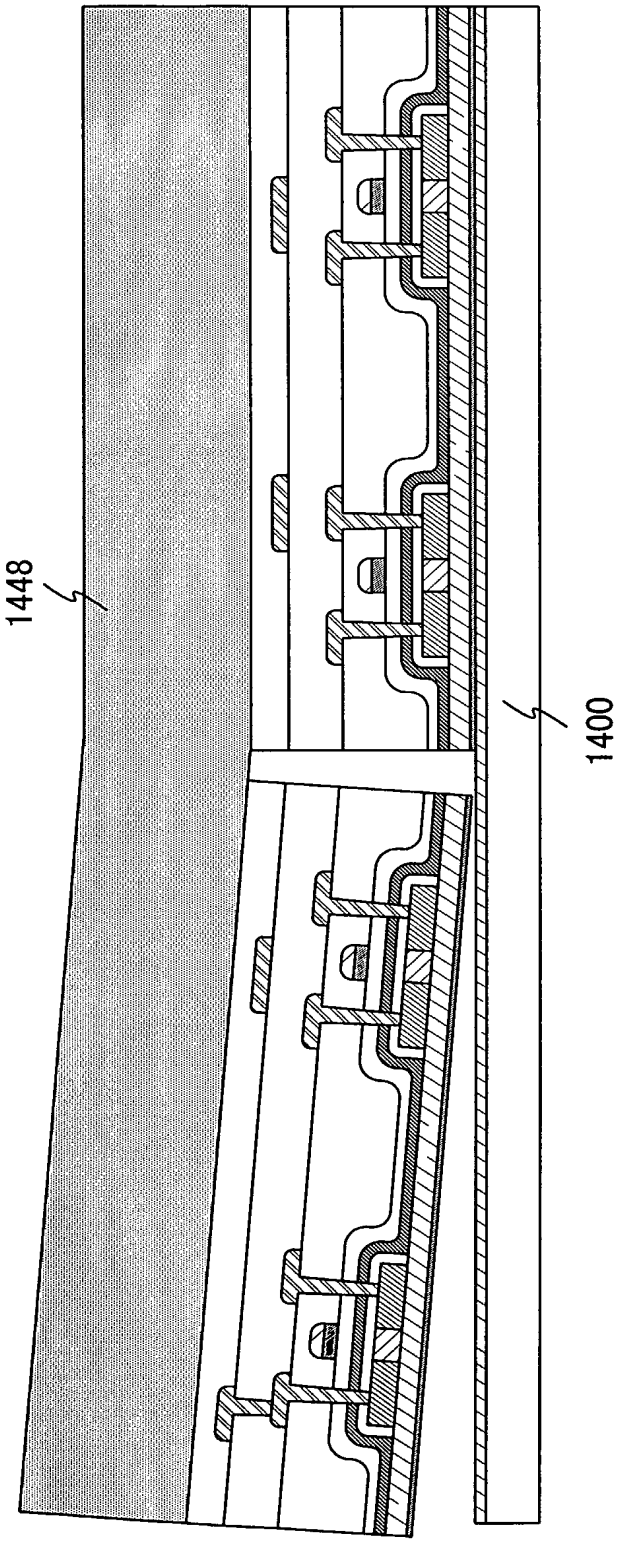


FIG. 17B

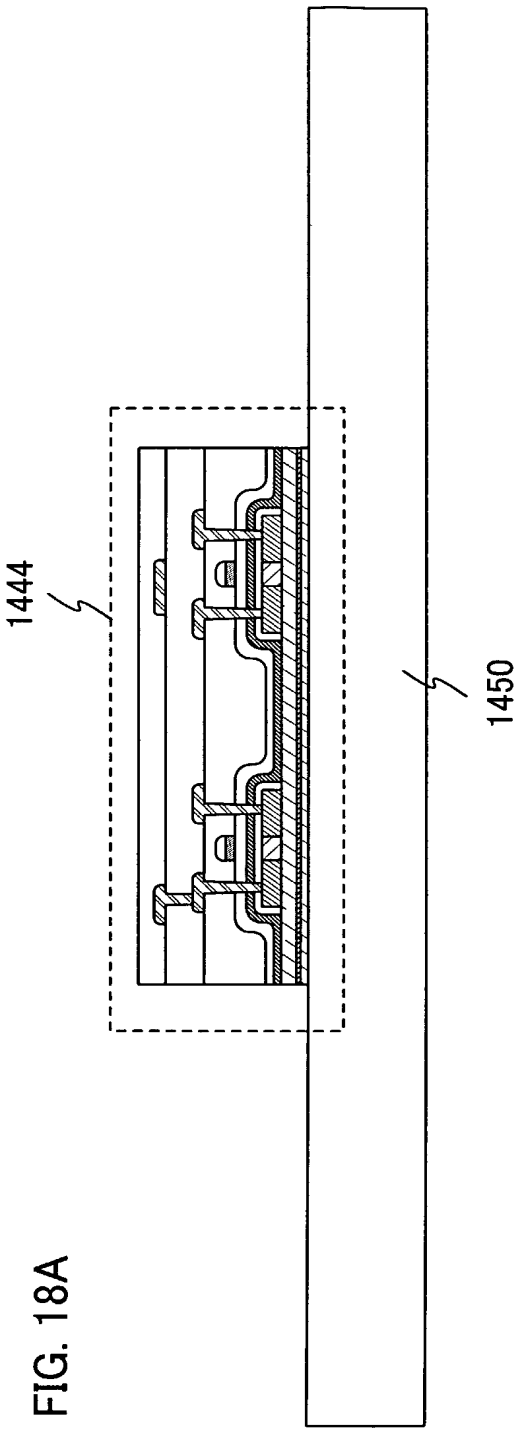


FIG. 18A

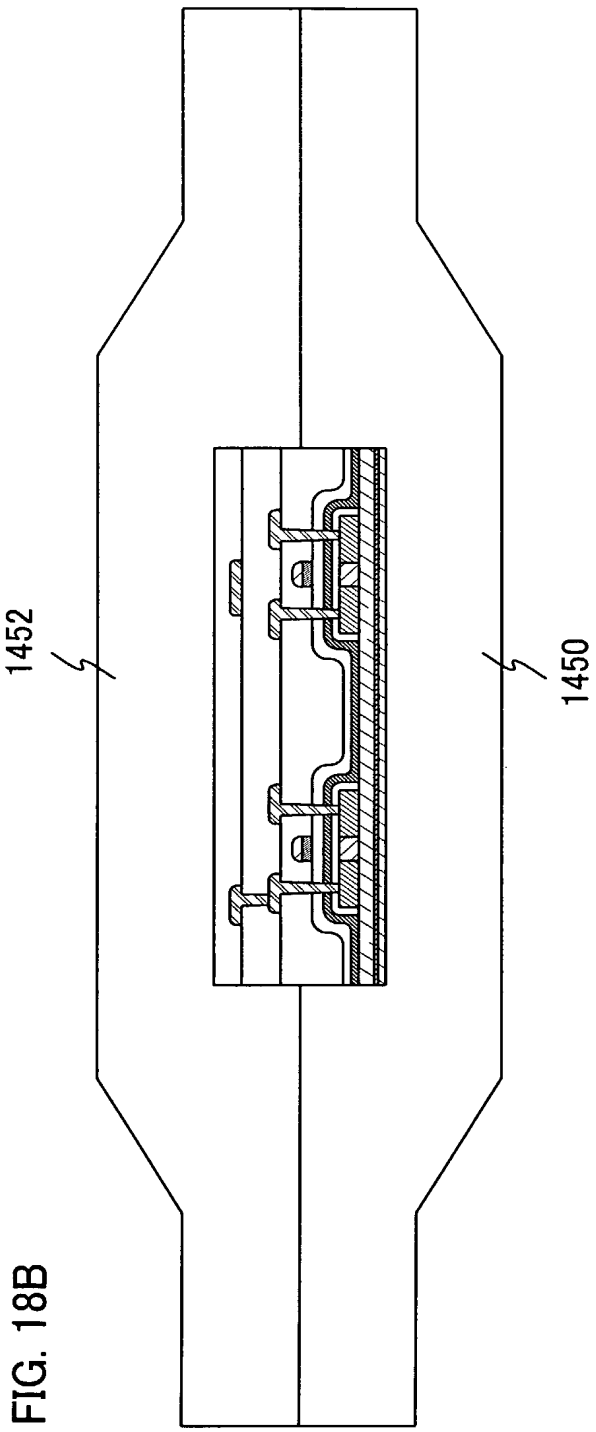


FIG. 18B

FIG. 19A

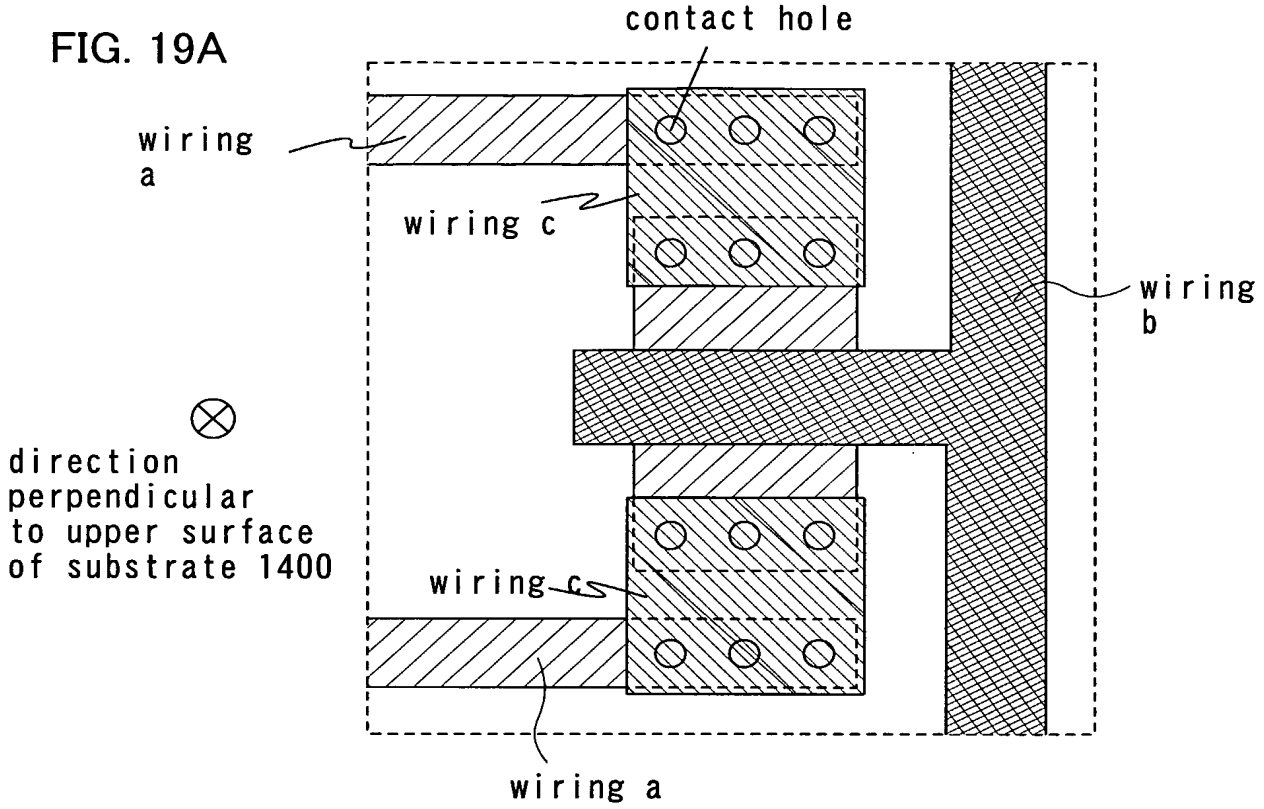


FIG. 19B

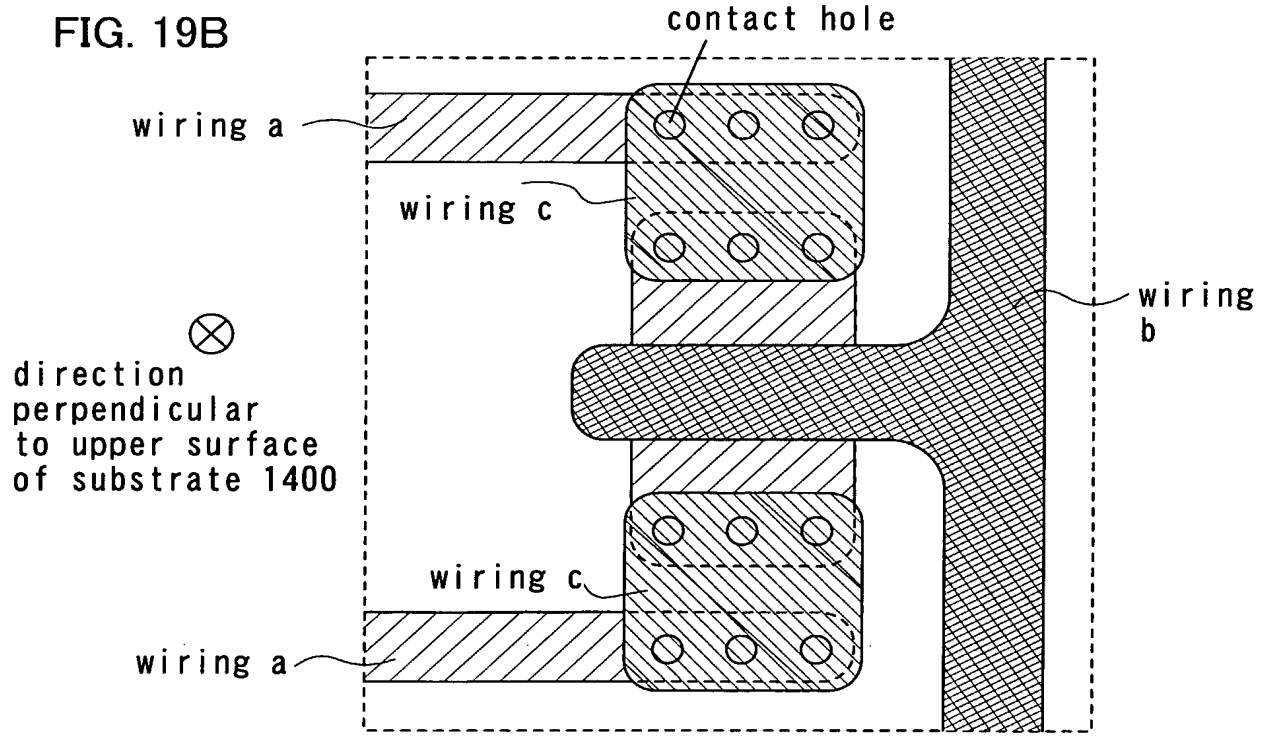


FIG. 20A

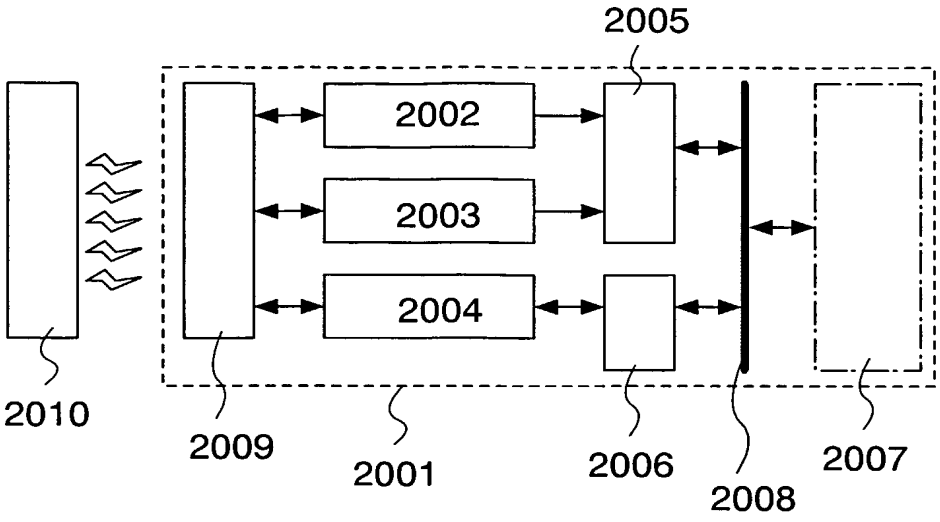


FIG. 20B

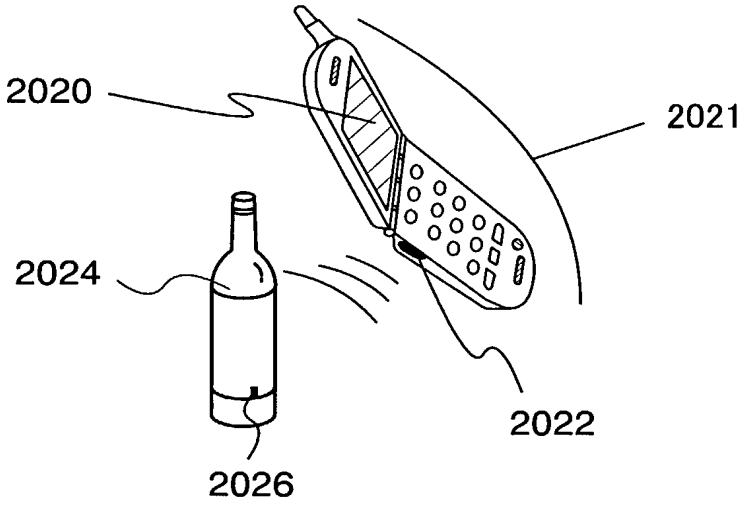
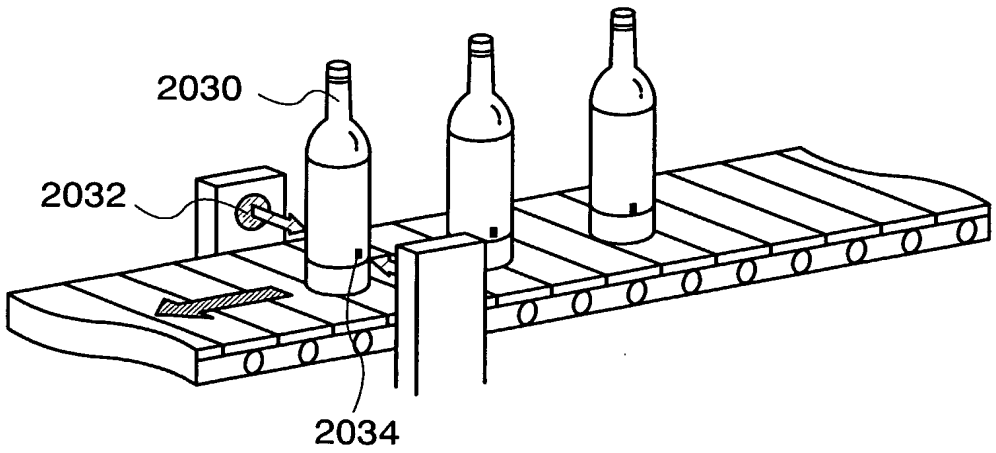


FIG. 20C



101: LASER OSCILLATOR, 102: LASER OSCILLATOR, 103: SLIT, 104: MIRROR, 105: LINEAR OR RECTANGULAR BEAM, 106: CYLINDRICAL LENS, 107: CYLINDRICAL LENS, 108: LINEAR OR RECTANGULAR BEAM, 109: OPTICAL FIBER, 110: BEAM SPOT, 111: SUBSTRATE, 112: SUCTION STAGE, 113: X-STAGE, 114: Y-STAGE, 201: LASER OSCILLATOR, 202: LASER OSCILLATOR, 203: DIFFRACTIVE OPTICAL ELEMENT, 205: SLIT, 206: MIRROR, 207: BEAM, 208: CONDENSING LENS, 209: CONDENSING LENS, 210: BEAM, 211: OPTICAL FIBER, 212: BEAM SPOT, 213: SUCTION STAGE, 214: SUBSTRATE, 215: X-STAGE, 216: Y-STAGE, 401: SLIT OPENING PORTION, 402: BLOCKING FILM, 501: LASER, 502: LASER, 503: OPTICAL ISOLATOR, 504: OPTICAL ISOLATOR, 505: BEAM EXPANDER, 506: BEAM EXPANDER, 507: BEAM EXPANDER, 508: BEAM EXPANDER, 509: MIRROR, 510: MIRROR, 511: MIRROR, 512: MIRROR, 513: DUMPER, 514: DUMPER, 515: SLIT, 516: LASER BEAM, 517: MIRROR, 518: CYLINDRICAL LENS, 519: CYLINDRICAL LENS, 520: SUBSTRATE, 521:BEAM SPOT, 522: LASER OSCILLATOR, 523: OPTICAL FIBER, 524: BEAM SPOT, 525: SUCTION STAGE, 526: X-STAGE, 527: Y-STAGE, 700: SUBSTRATE, 701: BASE FILM, 702: AMORPHOUS SEMICONDUCTOR FILM, 703: LASER, 704: SPHERICAL LENS, 705: LASER, 706: CRYSTALLINE SEMICONDUCTOR FILM, 707: ISLAND-SHAPED SEMICONDUCTOR FILM, 708: GATE INSULATING FILM, 709: GATE ELECTRODE, 710: SOURCE REGION, 711: DRAIN REGION, 712: LDD REGION, 713: N-CHANNEL TFT, 714: N-CHANNEL TFT, 715: P-CHANNEL TFT, 716: INSULATING FILM, 717: INSULATING FILM, 718: WIRING, 719: INSULATING FILM, 801: SEMICONDUCTOR FILM, 802: BEAM SPOT BY

HARMONIC, 803: BEAM SPOT BY FUNDAMENTAL WAVE, 804: BEAM SPOT BY HARMONIC, 805: BEAM SPOT BY HARMONIC, 806: BEAM SPOT BY HARMONIC, 807: LASER PITCH, 808: LASER-OVERLAPPING REGION, 901: SOURCE SIGNAL LINE, 902: GATE SIGNAL LINE, 903: CURRENT SUPPLYING LINE, 904: SWITCHING TFT, 905: DRIVER TFT, 906: CAPACITOR, 907: LIGHT-EMITTING ELEMENT, 1001: CASE, 1002: SUPPORTING STAND, 1003: DISPLAY PORTION, 1004: SPEAKER PORTIONS, 1005: VIDEO INPUT TERMINAL, 1011: CASE, 1012: DISPLAY PORTION, 1013: KEYBOARD, 1014: EXTERNAL CONNECTION PORT, 1015: POINTING MOUSE, 1041: PASSPORT, 1042: IC TAG, 1051: IC TAG, 1052: READER, 1053: ANTENNA PORTION, 1054: DISPLAY PORTION, 1101: BEAM SPOT, 1102: ENERGY DENSITY DISTRIBUTION, 1103: CENTER REGION OF BEAM SPOT, 1104: END REGION OF BEAM SPOT, 1200: SUBSTRATE, 1201: BASE FILM, 1202: SEMICONDUCTOR FILM, 1203: CRYSTALLIZED FILM, 1204: TWO LASER BEAMS, 1205: SEMICONDUCTOR FILM, 1206: OXIDE FILM, 1207: SEMICONDUCTOR FILM FOR GETTERING, 1208: ISLAND-SHAPED SEMICONDUCTOR FILM, 1400: FIRST SUBSTRATE, 1402: INSULATING FILM, 1404: PEELING LAYER, 1406: INSULATING FILM, 1408: SEMICONDUCTOR FILM, 1410: CRYSTALLINE SEMICONDUCTOR FILM, 1412: FIRST SEMICONDUCTOR FILM, 1414: SECOND SEMICONDUCTOR FILM, 1416: RESIST MASK, 1418: FIRST INSULATING FILM, 1420: FIRST INSULATING FILM, 1422: SECOND INSULATING FILM, 1424: THIRD INSULATING FILM, 1426: CONDUCTIVE FILM, 1426a: FIRST CONDUCTIVE FILM,

1428:CONDUCTIVE FILM, 1428a: SECOND CONDUCTIVE FILM, 1430: INSULATING FILM, 1432: CONDUCTIVE FILM, 1434: THIN FILM TRANSISTOR, 1436: THIN FILM TRANSISTOR, 1438: INSULATING FILM, 1440: CONDUCTIVE FILM, 1442: INSULATING FILM, 1444: ELEMENTS, 1446: OPENING PORTION, 1448: FIRST SHEET MATERIAL, 1450: SECOND SHEET MATERIAL, 1452: THIRD SHEET MATERIAL, 2001: RADIO FREQUENCY IC TAG, 2002: POWER SOURCE CIRCUIT, 2003: CLOCK GENERATOR CIRCUIT, 2004: CLOCK GENERATOR CIRCUIT, 2005: CONTROL CIRCUIT, 2006: INTERFACE CIRCUIT, 2007: MEMORY, 2008: DATA BUS, 2009: ANTENNA, 2010: READER/WRITER, 2020: DISPLAY PORTION, 2021: MOBILE TERMINAL, 2022: READER/WRITER, 2024: OBJECT, 2026: RADIO FREQUENCY IC TAG, 2030: OBJECT, 2032: READER/WRITER, 2034: RADIO FREQUENCY IC TAG